Influence of Excited States of Mg Acceptor on Hole Concentration in GaN

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Ground and excited states of Acceptor in GaN Hydrogenic model  $\Delta E_r = 13.6 \frac{m}{m_0 \epsilon_s^2} \cdot \frac{1}{r^2} \text{ eV}$ Acceptor Level (ground state level) First excited state level  $\Delta E_{\rm A} = \Delta E_1 = 100 {\rm meV}$  $\Delta E_2 = 25 \text{ meV}$ In the case of p-type GaN In the case of B-doped Si  $\Delta E_{\rm A}$ 100 meV  $\int \frac{\Delta E_A}{45 \text{ meV}}$  $\downarrow 1 25 \text{ meV}^{\Delta E_2}$  $E_{V}$  $E_{v}$ 

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Conventional distribution function including the influence of excited states

$$f_{\rm conv}(\Delta E_{\rm A}) = \frac{1}{1 + 4\left\{\exp\left(\frac{\Delta E_{\rm A} - \Delta E_{\rm F}}{kT}\right) + \sum_{r=2}^{2} g_r \exp\left(\frac{\Delta E_r - \Delta E_{\rm F}}{kT}\right)\right\}}$$

Hardly any holes can be emitted into the valence band, because they are captured in the excited states.

 $N_A$  higher than  $N_A$  obtained by the FD distribution function is required in order to meet p(T).

R. A. Smith, Semiconductors, 2<sup>nd</sup> ed. (Cambridge University Press, 1978) p. 92.

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# **Proposed distribution function**

including the influence

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$$f(\Delta E_A) = \frac{1}{1 + 4\exp\left(-\frac{\overline{E_{ex}}}{kT}\right) \cdot \left\{\exp\left(\frac{\Delta E_A - \Delta E_F}{kT}\right) + \sum_{r=2}^{1} g_r \exp\left(\frac{\Delta E_r - \Delta E_F}{kT}\right)\right\}}$$

This term makes acceptors release holes

at high temperatures more easily than  $f_{conv}(\Delta E_A)$ . Ensemble average of ground and excited state levels

$$\overline{E_{\text{ex}}} = \frac{\sum (\Delta E_{\text{A}} - \Delta E_{r}) g_{r} \exp \left(-\frac{\Delta E_{\text{A}} - \Delta E_{r}}{kT}\right)}{g_{1} + \sum_{r=2}^{\infty} g_{r} \exp \left(-\frac{\Delta E_{\text{A}} - \Delta E_{r}}{kT}\right)}$$

Average acceptor level:  $\overline{\Delta E_A} = \Delta E_A - \overline{E_{ex}}$ 

H. Matsuura, New Journal of Physics, 4 (2002) 12.1 (http://www.njp.org/)

## Experimental

Conditions of Mg-doped GaN epilayer

	T <sub>s</sub> [°C]	TMGa [µmol/min]	CP <sub>2</sub> Mg [µmol/min]	V/III	Thickness [µm]
Mg-doped GaN	1025	360.3	5	1700	2
Undoped GaN	1025	360.3	0	1700	1
GaN buffer	515	131.3	0	4600	0.03
Sapphire (0001)					

Annealing conditions: 800 °C, 20 min Hall-effect measurement: 125 K~295 K 1.4 T

How to determine  $\Delta E_A$  and  $N_A$  using p(T)Free Carrier Concentration Spectroscopy (FCCS)



# Results obtained by FCCS in GaN

	$N_{A}$ [cm <sup>-3</sup> ]	$\Delta E_{\rm A} [{\rm meV}]$	N <sub>comp</sub> [cm <sup>-3</sup> ]
$f(\Delta E_A)$	8.9x10 <sup>18</sup>	149	$1.5 \mathrm{x} 10^{17}$
$f_{FD}(\Delta E_A)$	2.1x10 <sup>20</sup>	154	$2.2 \times 10^{18}$

The concentration of Mg is  $\sim 2 \times 10^{19}$  cm<sup>-3</sup>

determined by SIMS

In the case of  $f(\Delta E_A)$ ,  $N_A$  is reasonable. (44.5 % of Mg atoms are located at the substitutional sites in GaN) In the case of  $f_{FD}(\Delta E_A)$ ,  $N_A$  is rather high.

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## p(T) simulated using the obtained values



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### Simulated FCCS signals



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## Summary

In order to obtain the reliable acceptor density from p(T), a distribution function including the influence of the excited states of acceptors is found to be required.

In order to investigate the influence of the excited states, FCCS is considered to be more appropriate than the curve fitting procedure of p(T).

In the conditions of this Mg-doped epilayer, 44.5 % of the doped Mg atoms are found to behave like an acceptor in GaN.